

WEST Search History

DATE: Wednesday, August 03, 2005

Hide?	<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>
		<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L38	136 and (wash\$3 or rins\$3)	15
		<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L37	((semiconductor or wafer or substrate) with polish\$3) same alcohol) and (ethylene oxide)	4
		<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L36	((semiconductor or wafer or substrate) with polish\$3) same alcohol) and (ethylene oxide)	49
		<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L35	((semiconductor or wafer or substrate) with polish\$3) same alcohol) and (ethylene oxide)	53
<input type="checkbox"/>	L34	((semiconductor or wafer or substrate) with polish\$3) same alcohol) and (dihydrooxirene or (dimethylene oxide) or epoxyethane or 1,2-epoxyethane or (ethene oxide) or oxacyclopropane or oxane or oxidoethane or amprolene or anproline or oxirane)	4
		<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L33	(semiconductor or wafer or substrate) same polish\$3 same (dihydrooxirene or (dimethylene oxide) or epoxyethane or 1,2-epoxyethane or (ethene oxide) or oxacyclopropane or oxane or oxidoethane or amprolene or anproline or oxirane)	0
		<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L32	(semiconductor or wafer or substrate) same polish\$3 same (dihydrooxirene or (dimethylene oxide) or epoxyethane or 1,2-epoxyethane or (ethene oxide) or etO or oxacyclopropane or oxane or oxidoethane or amprolene or anproline or oxirane)	18
<input type="checkbox"/>	L31	L30 same (dihydrooxirene or (dimethylene oxide) or epoxyethane or 1,2-epoxyethane or (ethene oxide) or etO or oxacyclopropane or oxane or oxidoethane or amprolene or anproline or oxirane)	0
<input type="checkbox"/>	L30	(semiconductor or wafer or substrate or workpiece) same polish\$3 same alcohol same (rins\$3 or wash\$3)	345
<input type="checkbox"/>	L29	L27 and (dihydrooxirene or (dimethylene oxide) or epoxyethane or 1,2-epoxyethane or (ethene oxide) or etO or oxacyclopropane or oxane or oxidoethane or amprolene or anproline or oxirane)	5
<input type="checkbox"/>	L28	L27 same (dihydrooxirene or (dimethylene oxide) or epoxyethane or 1,2-epoxyethane or (ethene oxide) or etO or oxacyclopropane or oxane or oxidoethane or amprolene or anproline or oxirane)	0
<input type="checkbox"/>	L27	(semiconductor or wafer or substrate or workpiece) same (polish\$3 with steps) same alcohol same (rins\$3 or wash\$3)	54

<input type="checkbox"/>	L26	L25 and l12	10
<input type="checkbox"/>	L25	((semiconductor or wafer or substrate or workpiece) same polish\$3) and (octanol or (octyl alcohol) or 1-Octanol or (Caprylic alcohol) or (Heptyl carbinol) or 1-Hydroxyoctane)	223
		<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L24	((semiconductor or wafer or substrate or workpiece) same polish\$3 same (rins\$3 or wash\$3)) and (octanol or (octyl alcohol) or 1-Octanol or (Caprylic alcohol) or (Heptyl carbinol) or 1-Hydroxyoctane)	27
<input type="checkbox"/>	L23	((semiconductor or wafer or substrate or workpiece) with polish\$3 with (rins\$3 or wash\$3)) and (octanol or (octyl alcohol) or 1-Octanol or (Caprylic alcohol) or (Heptyl carbinol) or 1-Hydroxyoctane)	11
<input type="checkbox"/>	L22	((semiconductor or wafer or substrate or workpiece) with polish\$3) and (octanol or (octyl alcohol) or 1-Octanol or (Caprylic alcohol) or (Heptyl carbinol) or 1-Hydroxyoctane)	135
<input type="checkbox"/>	L21	(semiconductor or wafer or substrate or workpiece) same polish\$3 same (octanol or (octyl alcohol) or 1-Octanol or (Caprylic alcohol) or (Heptyl carbinol) or 1-Hydroxyoctane)	7
		<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L20	((semiconductor or wafer or substrate or workpiece) with polish\$3) same (octanol or (octyl alcohol) or 1-Octanol or (Caprylic alcohol) or (Heptyl carbinol) or 1-Hydroxyoctane)	3
<input type="checkbox"/>	L19	(semiconductor or wafer or substrate or workpiece) same polish\$3 same(octanol or (octyl alcohol))	7
<input type="checkbox"/>	L18	14 and (polish\$3 same(octanol or (octyl alcohol)))	0
		<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L17	19 and (octanol or (octyl alcohol))	0
<input type="checkbox"/>	L16	19 and (octanol or (alkyl alcohol))	1
<input type="checkbox"/>	L15	19 same (octanol or (alkyl alcohol))	0
<input type="checkbox"/>	L14	110 same (octanol or (alkyl alcohol))	0
<input type="checkbox"/>	L13	L12 and l10	24
<input type="checkbox"/>	L12	510/175;134/2,6,26;438/690,691,692,693.ccls.	8953
		<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L11	(polish\$3 with steps) same surfactant same (rins\$3 or wash\$3)	5
		<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L10	(polish\$3 with steps) same surfactant same (rins\$3 or wash\$3)	83
		<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L9	(polish\$3 with steps) same surfactant same (rins\$3 or wash\$3)	88
<input type="checkbox"/>	L8	(polish\$3 with steps with plural\$3) same surfactant same (rins\$3 or wash\$3)	0
<input type="checkbox"/>	L7	L4 and (polish\$3 same surfactant same (rins\$3 or wash\$3))	3
<input type="checkbox"/>	L6	L4 and (polish\$3 same surfactant same rins\$3)	3
<input type="checkbox"/>	L5	L4 and (polish\$3 with surfactant with rins\$3)	0
<input type="checkbox"/>	L4	Taiwan semiconductor manufacturing	11290

<input type="checkbox"/>	L3	L1 and (polish\$3 with surfactant)	4
<input type="checkbox"/>	L2	L1 and (polish\$3 with surfactant with rins\$3)	0
<input type="checkbox"/>	L1	chen-ying-ho\$.in.	74

END OF SEARCH HISTORY